

the main mechanism for heat loss to the reflecting plate will be conduction through the gas.

B1
Can The thermal loading will, of course, depend upon the type of process gas and the chamber pressure during processing.

Replace the paragraph at page 6, line 21, with the following text:

B2
The temperatures at localized regions of the substrate 106 are measured by a plurality of temperature probes 152. Each temperature probe includes a sapphire light pipe 126 that passes through a conduit 124 that extends from the backside of the base 116 through the top of the reflector 102. The sapphire light pipe 126 is about 0.125 inch in diameter and the conduit 124 is slightly larger. The sapphire light pipe 126 is positioned within the conduit 124 so that its uppermost end is flush with or slightly below the upper surface of the reflector 102. The other end of light pipe 126 couples to a flexible optical fiber that transmits sampled light from the reflecting cavity to a pyrometer 128.

Replace the paragraph at page 9, line 13, with the following text:

B3
During processing, a process gas can be introduced into the space between the substrate and the window assembly through an inlet port. Gases are exhausted through an exhaust port, which is coupled to a vacuum pump (not shown).

Replace the paragraph at page 9, line 24, with the following text:

B4
A plurality of circular coolant passages 206 are also formed into the monolithic lamphead, in close proximity to the reflector cavities. The coolant passages transport a cooling fluid such as water. The cooling fluid is introduced into the coolant passages via an inlet 150 and removed at an outlet 152.
